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Over 10 μm grain size Sb_2Se_3 film and its effective surface passivation

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Outline

1

Superstrate: Large grain size film deposition

2

Substrate: Effective surface passivation method

3

Acknowledgements

Various advantages of Sb_2Se_3

Commercial prospect

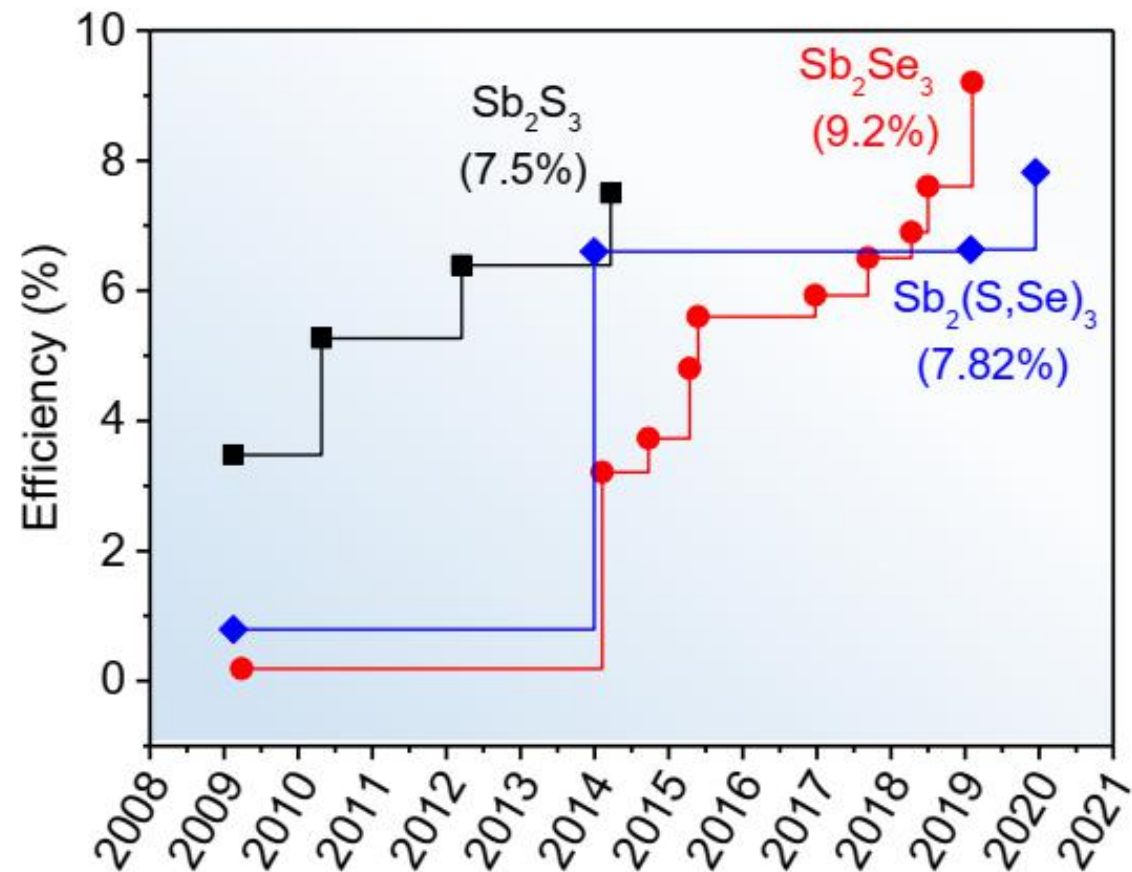
- Environmental-friendly
- Earth-abundant
- Low-cost

Easy for fabrication

- Low melting point ($\sim 615\text{ }^\circ\text{C}$)
- Binary compound (one phase)
- Stable in air

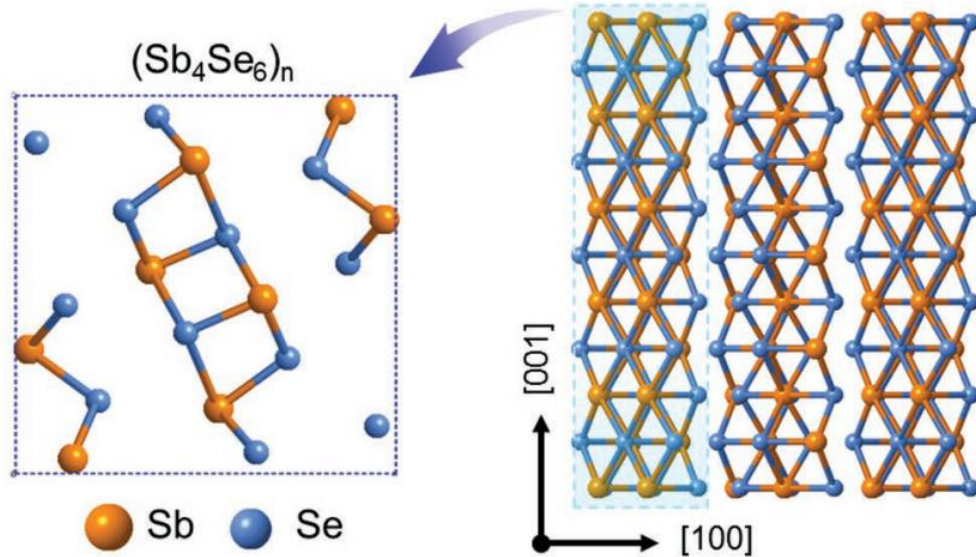
Potential in photovoltaic

- Bandgap of $\sim 1.1\text{ eV}$
- Absorption coefficient $> 10^5\text{ cm}^{-1}$

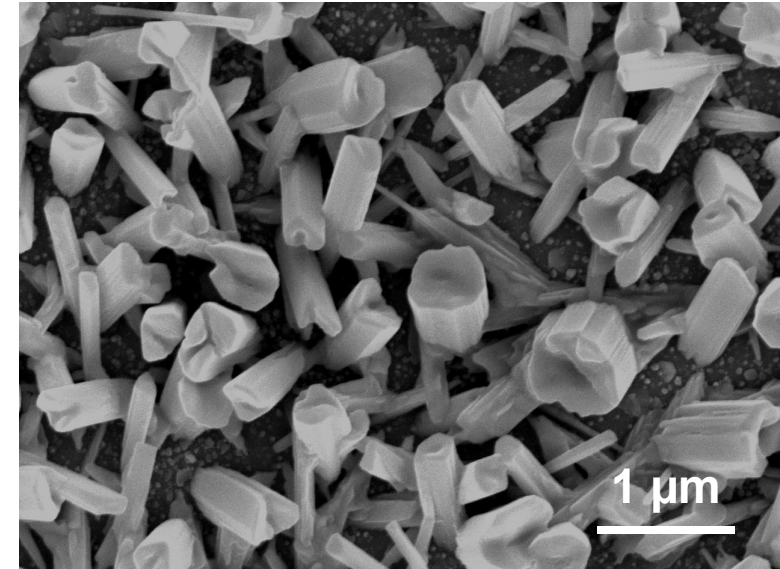


Rapid increase of PCE

The key challenge in Sb_2Se_3 film growth



Unique 1D structure



Rod-like Sb_2Se_3 film

Ideal orientation

$[\text{hk}0]$: parallel to substrate

$[\text{hk}1]$: incline to substrate

Compact film with large grain size

Sb-Se Bonding Energy > Van der Waal's Force

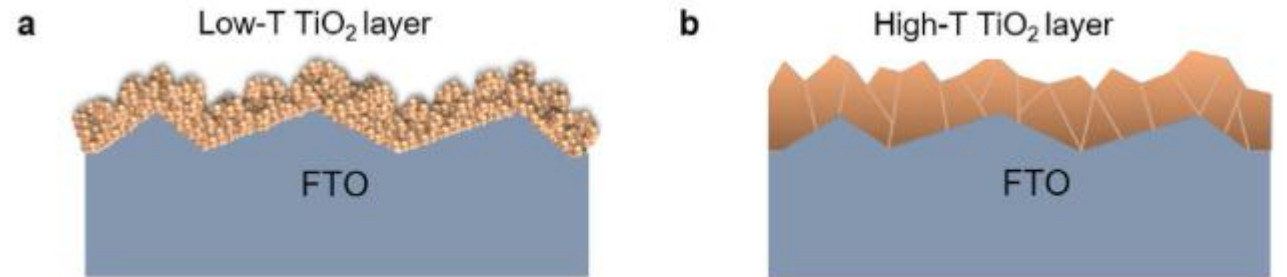
Prefer to grow along the chains (c-axis)

Our two strategies

More inert substrate

TiO₂ layer annealed at 550 °C

- Reduce the nucleation density



leadind to over 10 μm grain size Sb₂S₃ film

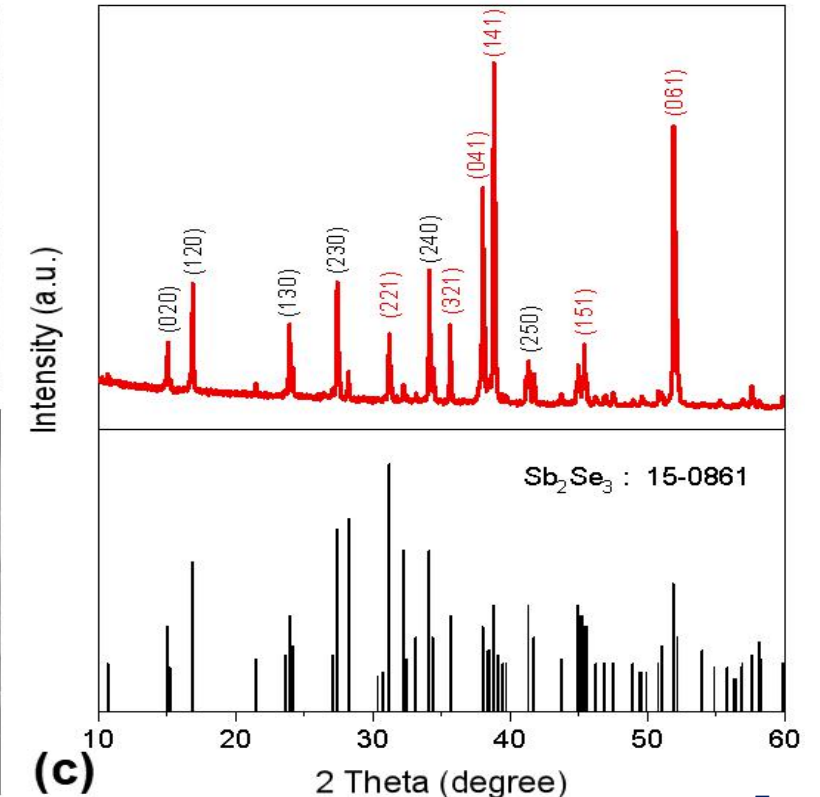
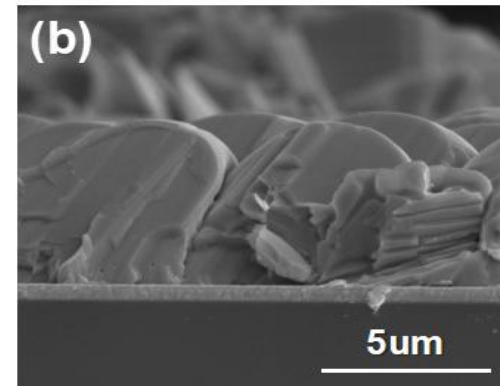
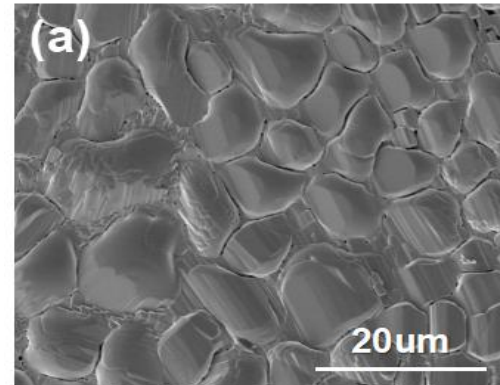
Close-spaced Sublimation

High substrate temp (400 °C)

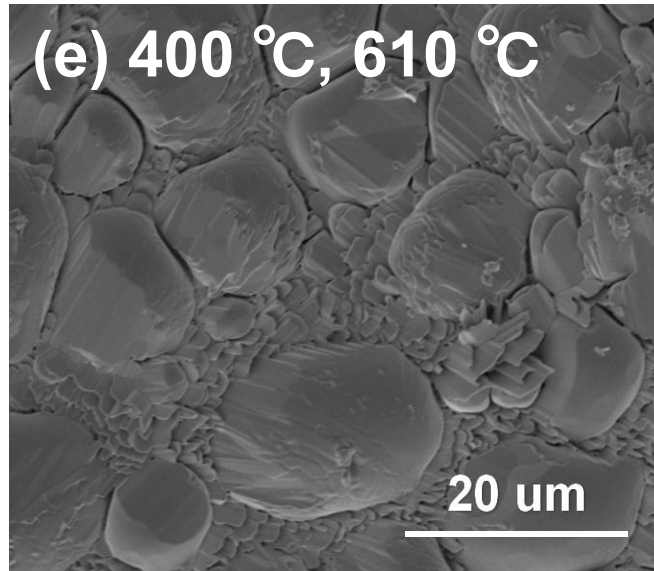
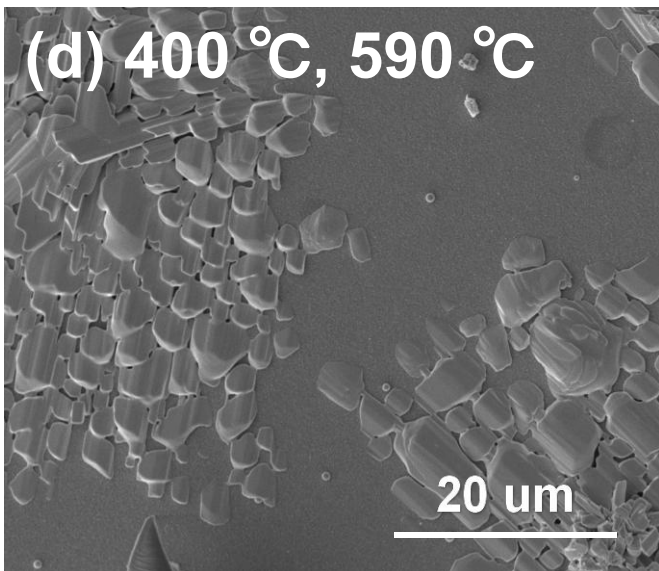
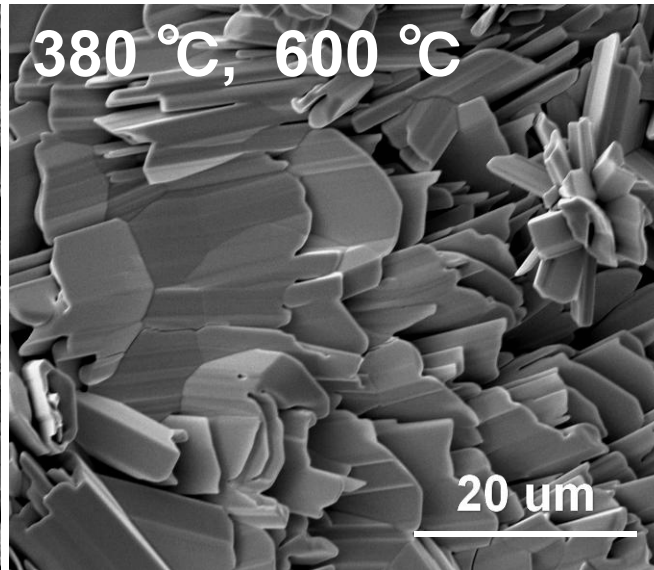
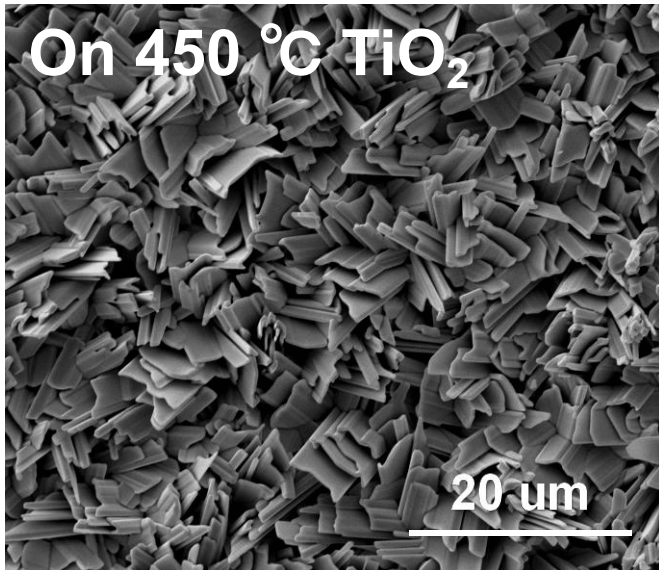
- Bonding with substrate
- Promote [hk1] orientation

High source temp (600 °C)

- Sufficient deposition rate
- Enhance grain size



Failed attempts



Too many nuclei

- Active substrate
- Lower substrate temp
- Rod-like or sheet-like

Improper source temp

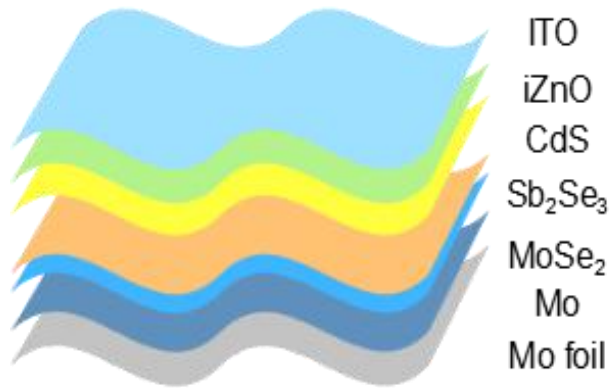
- Discontinuous film
- Small grains in gap

Summary

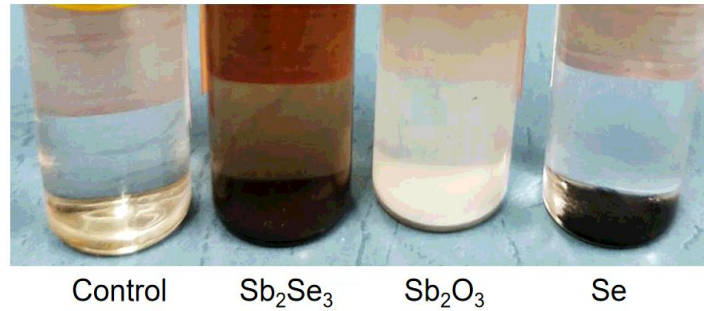
- Over 10 μm grain size compact Sb_2Se_3 film with [hk1] dominant orientation
- Key points:
 - Inert substrate: 550 °C annealed TiO_2 layer -> proper nucleation density
 - High substrate temp: 400 °C -> bonding with substrate
 - Appropriate source temp: 600 °C -> sufficient deposition rate
- However the PCE is low, possibly due to Se deficiency under high T_{sub}

400C, 600C	Voc (V)	Jsc (mA/cm ²)	FF (%)	Eff (%)
Highest	0.315	15.9	43.1	2.16
V.A.	0.324	12.3	43.4	1.73
SD/VA.	0.045	0.184	0.018	0.202

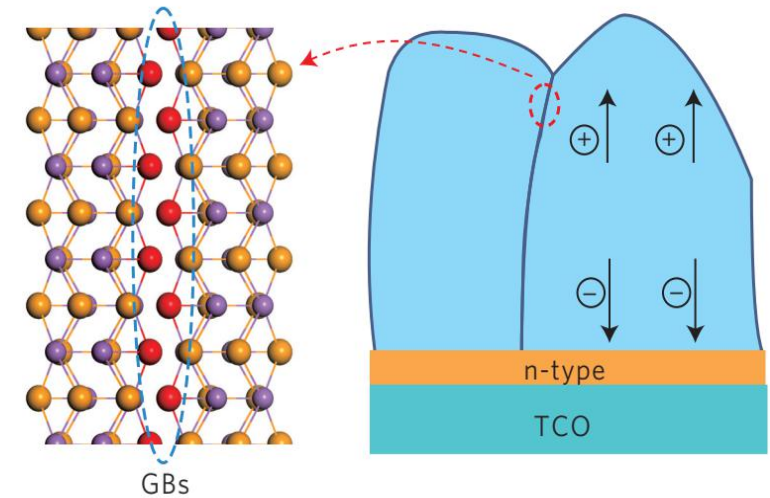
The importance of surface passivation



NH₃·H₂O
25% wt

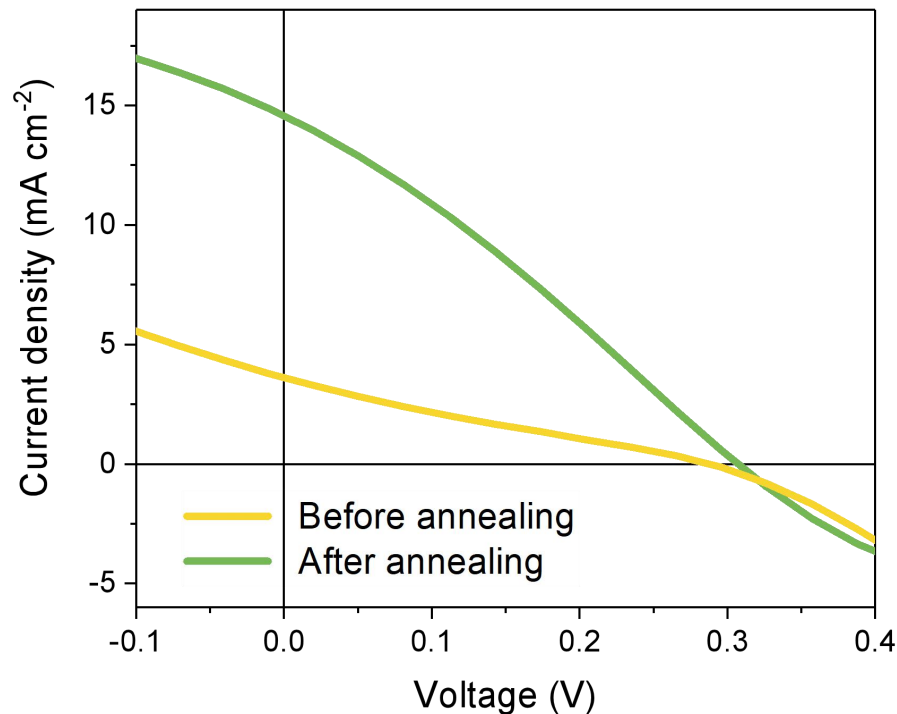


Sb₂Se₃ is dissoluble in NH₃·H₂O

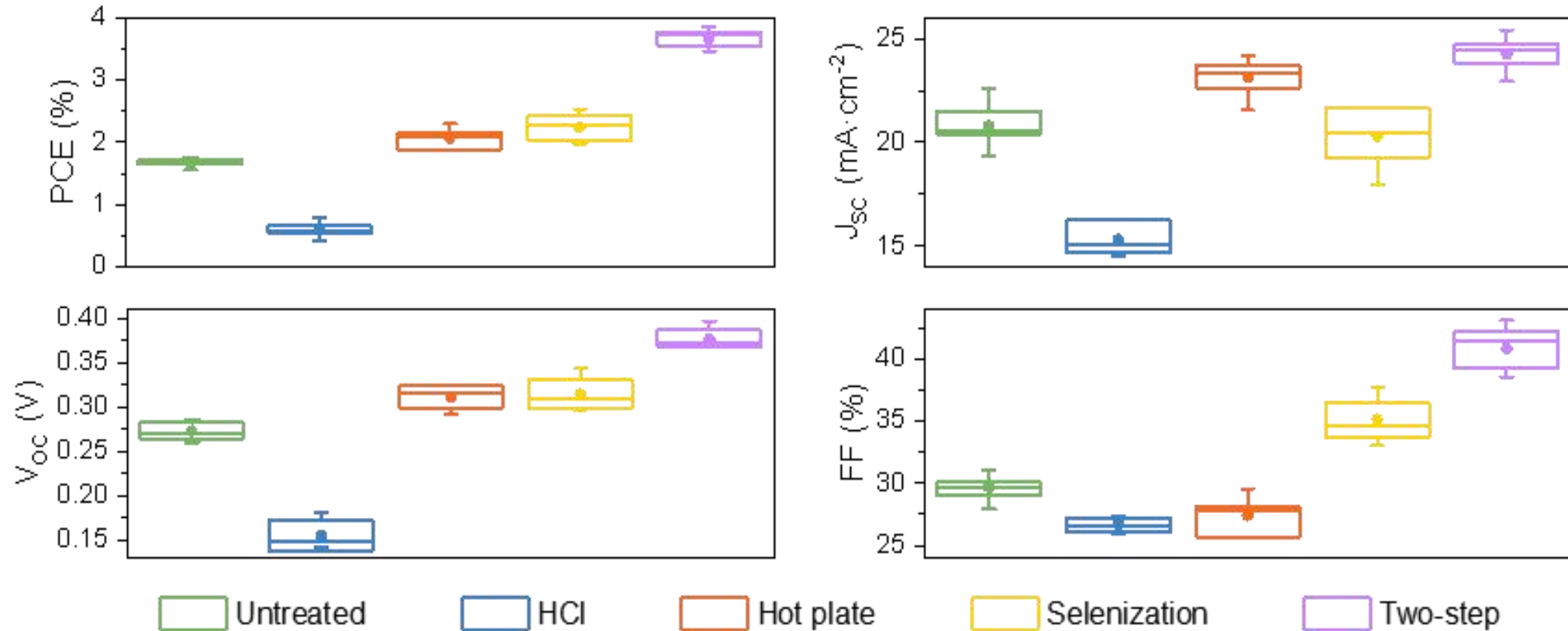


Extremely important in substrate structure

- CBD process damage Sb₂Se₃ surface
- Lots of dangling bonds on surface
- Surface defects block photo current

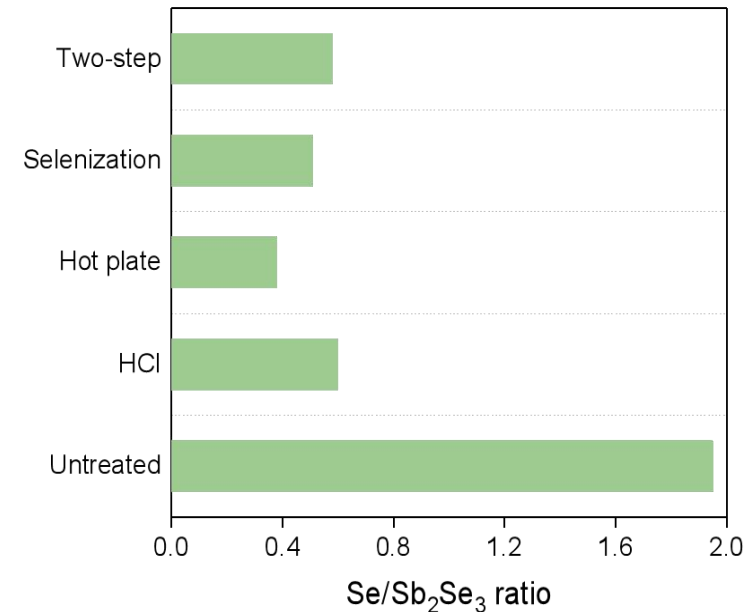
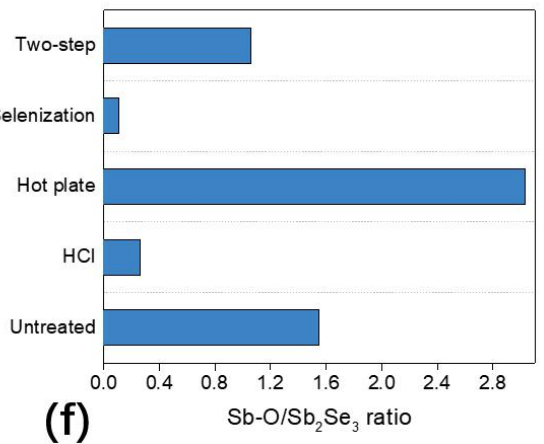
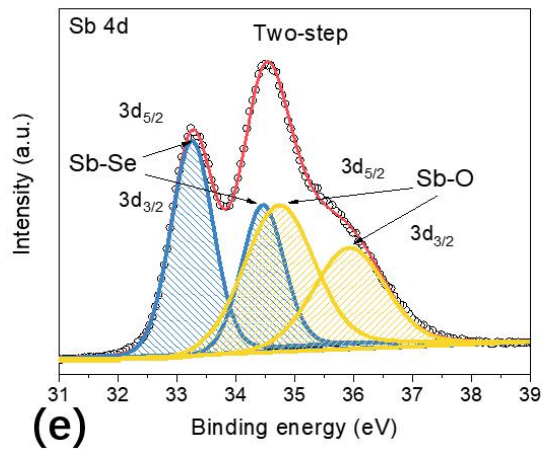
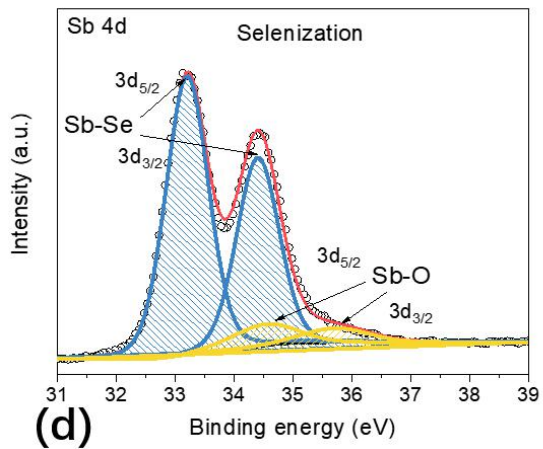
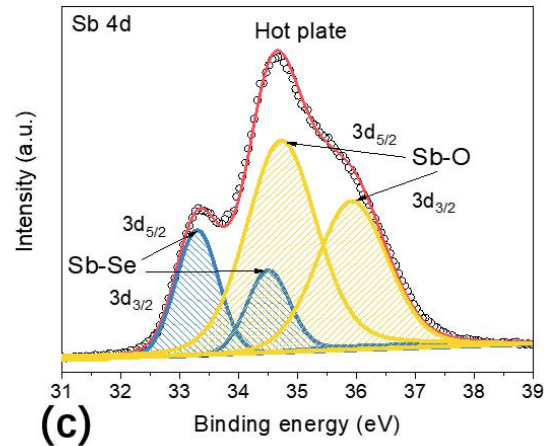
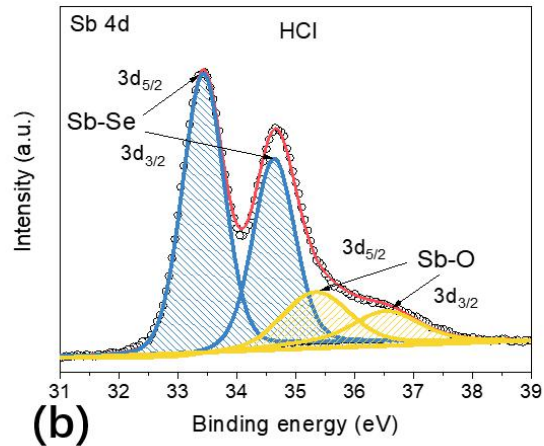
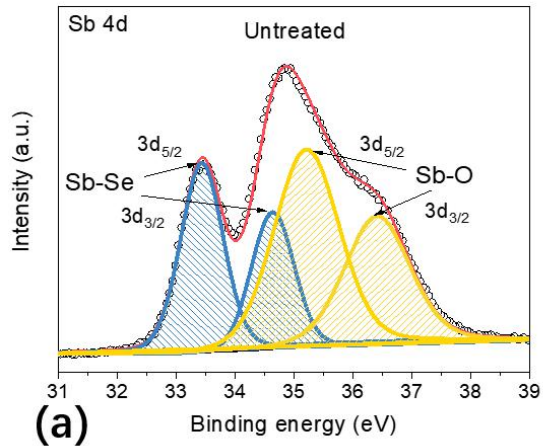


Four surface treatment attempts

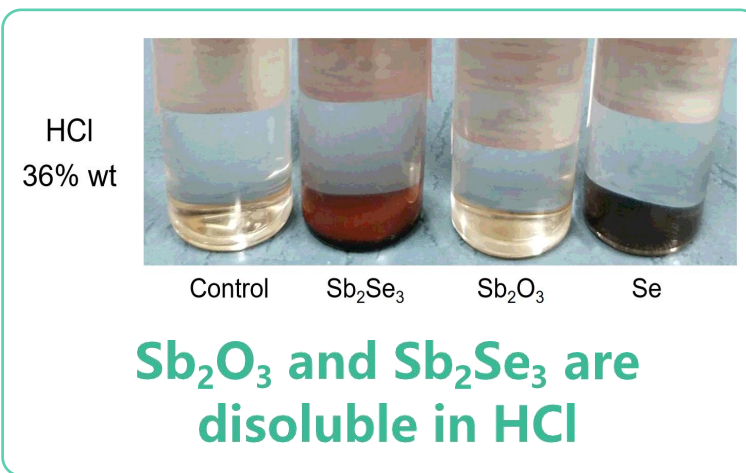


- Thermal evaporated In_2S_3 buffer layer was developed to avoid surface damage
- Two-step method is the best (HCl etching 30s; Hot plate 300 °C 60s in air)

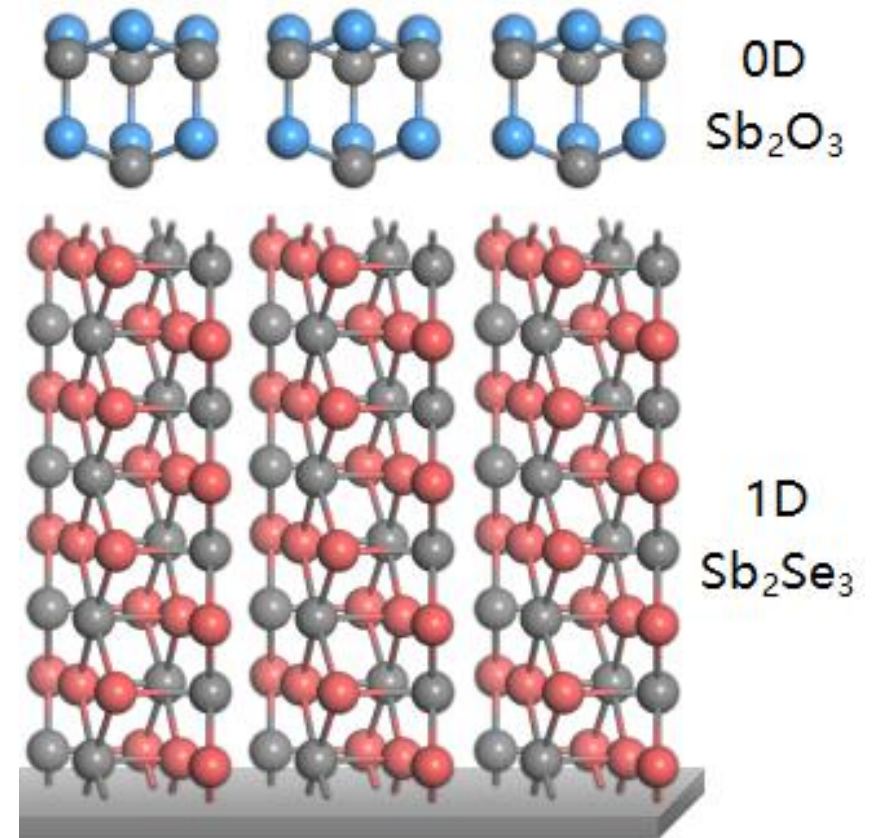
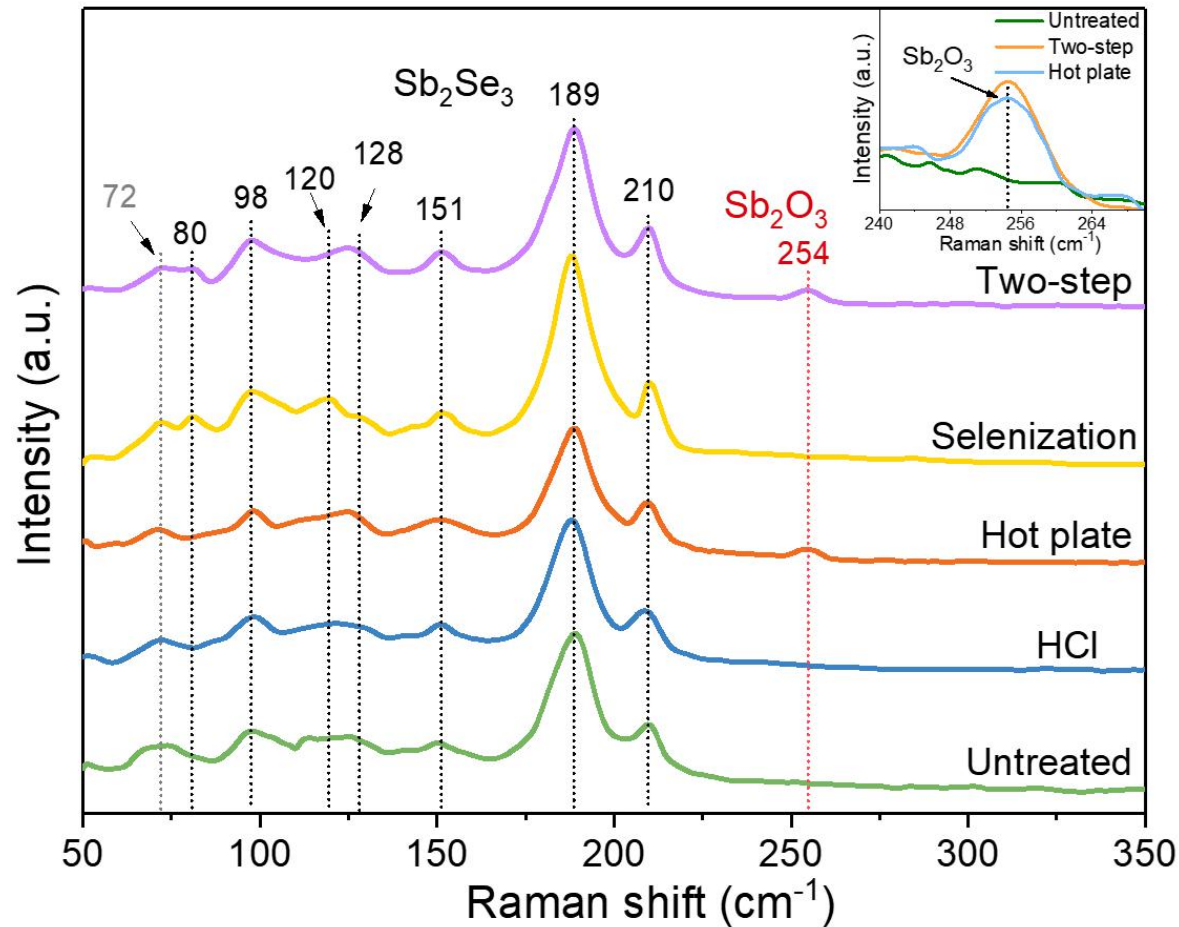
XPS analysing



- After treatment, Sb-O compound has significant difference
- Se compound is almost same between various method

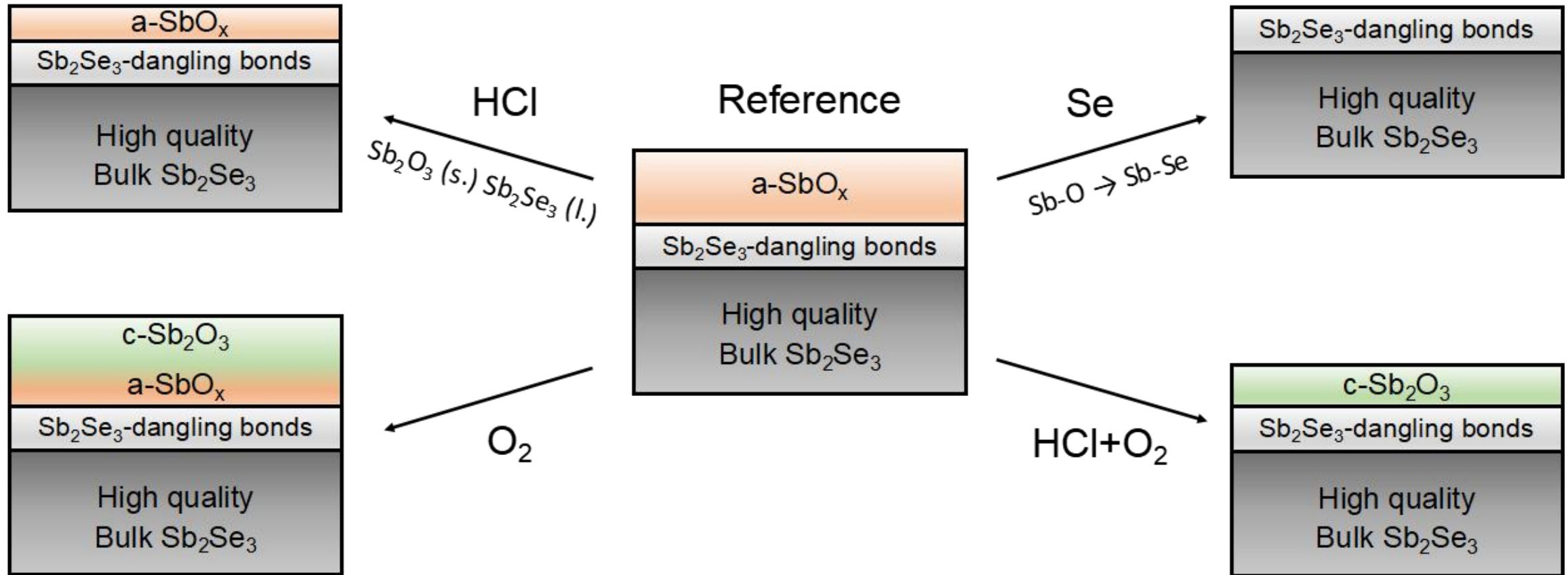


Raman spectrum and crystal structure



- Only high temperature annealed sample has Sb_2O_3 peak at 254 cm^{-1}
- Sb_2O_3 is 0D structure material without any dangling bonds

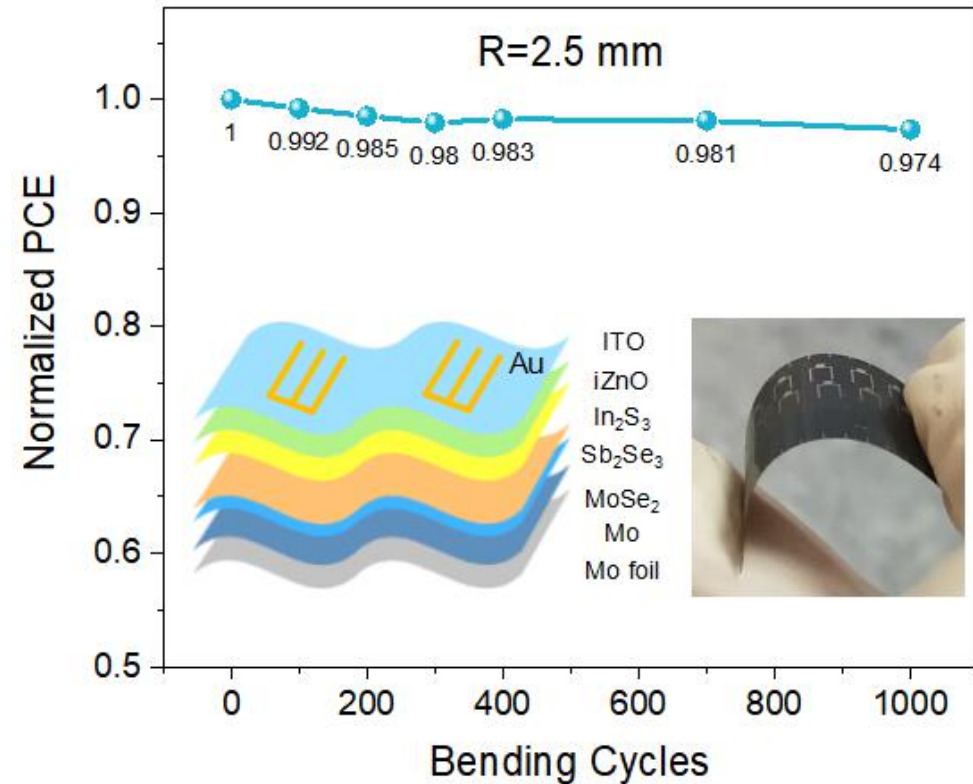
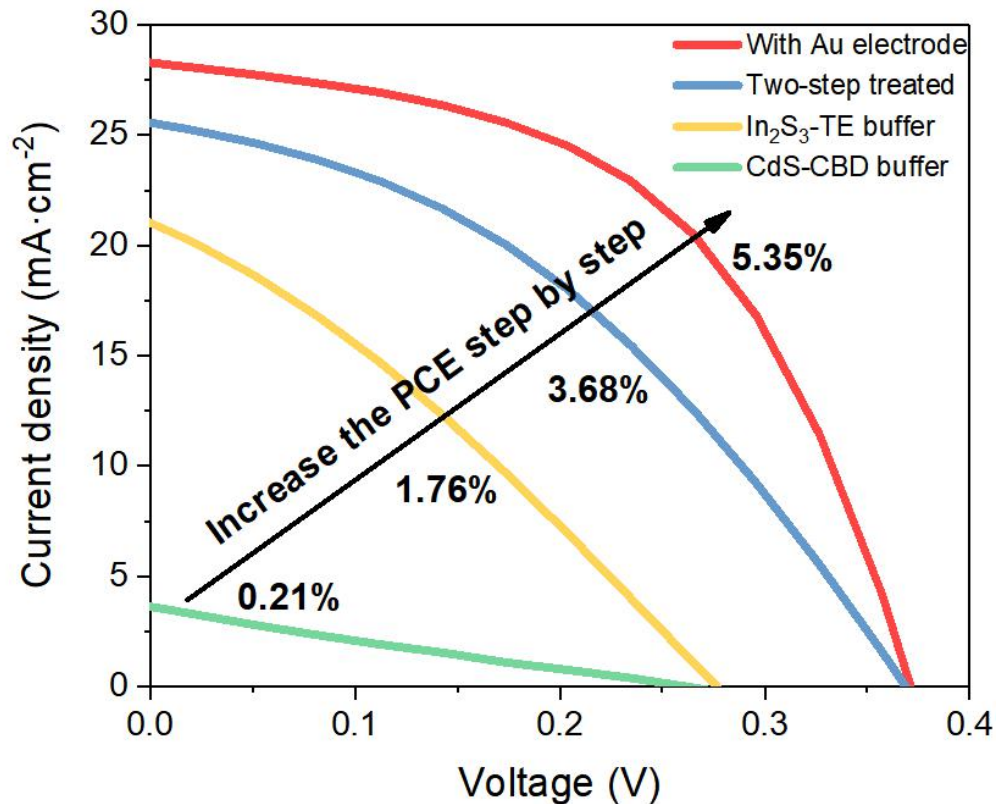
Passivation model



- Firstly, remove contaminative layer ($\text{a-Sb}_2\text{O}_3$) by HCl etching
- Secondly, form a high quality 0D $\text{c-Sb}_2\text{O}_3$ passivation layer on hot plate

Summary

- Thermal evaporated In_2S_3 non-toxic buffer layer was explored
- Simple two-step surface passivation method was developed
- 5.35% PCE flexible Sb_2Se_3 solar cell was fabricated



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Thanks for your attention!



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